Korean International Semiconductor Conference & Exhibition
on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[ThC2] Advanced Metrology & inspection, Process diagnostics & control, and Yield management VI

Session Date	November 13 (Thu.), 2025
Session Time	10:50-12:30
Session Room	Room C (Grand Ballroom 3, 2F)
Session Chair	Dr. Jeong Won Kim (KRISS, Korea)

[ThC2-1] [Invited] 10:50-11:20

Data-Driven Plasma Science-based Plasma Etching Process Design in OLED and Semiconductor Mass Productions Referring to PI-VM

Seolhye Park, Jaegu Seong, Yoona Park (Samsung Display Co., Ltd., Korea), Haneul Lee, Namjae Bae, Ji-Won Kwon, and Gon-Ho Kim (Seoul Nat'l Univ., Korea)

[ThC2-2] [Invited] 11:20-11:50

Advances in Plasma Diagnostics for Process Chamber Monitoring and Characterization: Microwave Diagnostics

Dae-Woong Kim (KIMM, Korea), SangHo Lee, InYong Park, GeonWoong Eom (KIMM and Chungnam Nat’l Univ., Korea), ShinJae You (Chungnam Nat’l Univ., Korea), Min Hur, and WooSeock Kang (KIMM, Korea)

[ThC2-3] 11:50-12:10

Photon Momentum Induced Particle Extraction in the Low-Pressure Plasma

Jun-Hyung Park and Hyo-Chang Lee (Korea Aerospace Univ., Korea)

[ThC2-4] 12:10-12:30

Development of Microwave Patch Antenna Sensor for Plasma Process Monitoring

Gwang-Seok Chae (Korea Aerospace Univ. and KRISS, Korea), Hee-Jung Yeom (KRISS, Korea), Min-Young Yoon (KFE, Korea), Eun-Seok Choe (KRISS and Chungnam Nat’l Univ., Korea), Jung-Hyung Kim (KRISS, Korea), and Hyo-Chang Lee (Korea Aerospace Univ., Korea)